

EAST Search History**EAST Search History (Prior Art)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	5	"551732".ap.	US-PGPUB; USPAT	ADJ	ON	2007/12/10 09:05
S2	6	("20050268999" "20070023281" "6331233" "6348113" "6348139" "7156963"). PN.	US-PGPUB; USPAT	ADJ	ON	2007/12/10 09:06
S3	154	148/668.ccls.	US-PGPUB; USPAT	ADJ	ON	2007/12/11 14:10
S4	63	148/668.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2007/12/11 14:10
S5	3	(tantalum or ta) and (nonrecryst\$8)	US-PGPUB; USPAT	ADJ	ON	2007/12/11 14:29
S6	16	(tantalum or ta) and (non-recryst\$8)	US-PGPUB; USPAT	ADJ	ON	2007/12/11 14:30
S7	0	148/668.ccls. and (tantalum or ta) and (non-recryst\$8 or nonrecryst\$8)	US-PGPUB; USPAT	ADJ	ON	2007/12/11 14:48
S8	273	204/298.12.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2007/12/11 15:04
S9	2	204/298.12.ccls. and (tantalum or ta) and (nonrecryst\$8 or non- recryst\$8)	US-PGPUB; USPAT	ADJ	ON	2007/12/11 15:04
S10	4	(sputter\$4 with target) and (non-recryst\$8 or nonrecryst\$8)	US-PGPUB; USPAT	ADJ	ON	2007/12/11 15:11
S11	8	(sputter\$4) and (non- recryst\$8 or nonrecryst\$8)	US-PGPUB; USPAT	ADJ	ON	2007/12/11 15:14
S12	1	ta sputtering targets method manufacturing	EPO	ADJ	ON	2007/12/11 15:20
S13	605	(tantalum or ta) and (sputter\$4 and (Vicker\$3 with hardness))	US-PGPUB; USPAT	ADJ	ON	2007/12/11 15:34
S14	143	((tantalum or ta) with (sputter\$4)) and (Vicker \$3 with hardness)	US-PGPUB; USPAT	ADJ	ON	2007/12/11 15:35
S15	1	("20030082864").PN.	US-PGPUB; USPAT	OR	OFF	2007/12/11 15:45

S16	1	("20070089815").PN.	US-PGPUB; USPAT	OR	OFF	2007/12/11 15:50
S17	1	("20050284546").PN.	US-PGPUB; USPAT	OR	OFF	2007/12/11 15:51
S18	1	("6193821").PN.	US-PGPUB; USPAT	OR	OFF	2007/12/11 15:55
S19	10	(sputter\$4) and (non-recrystal\$8 or nonrecrystal\$8)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/12/12 08:21
S20	313	tantalum and sputter\$4 target	JPO; DERWENT	ADJ	ON	2007/12/12 08:45
S21	12	tantalum and sputter\$4 target and \$4recrystal\$8	JPO; DERWENT	ADJ	ON	2007/12/12 08:46
S22	2	(sputter\$4) and (non-recrystal\$8 or nonrecrystal\$8)	EPO; JPO; DERWENT	ADJ	ON	2007/12/12 08:51
S23	4	(target) and (non-recrystal\$8 or nonrecrystal\$8)	EPO; JPO; DERWENT	ADJ	ON	2007/12/12 08:52
S24	55	(target) and (non-recrystal\$8 or nonrecrystal\$8)	US-PGPUB; USPAT	ADJ	ON	2007/12/12 08:57
S25	18	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8)	US-PGPUB; USPAT	ADJ	ON	2007/12/12 09:17
S26	924	(tantalum or ta) with hardness	US-PGPUB; USPAT	ADJ	ON	2007/12/12 09:37
S27	43	(tantalum or ta) with hardness with vicker	US-PGPUB; USPAT	ADJ	ON	2007/12/12 09:37
S28	57	(tantalum or ta) with hardness with vicker	JPO; DERWENT	ADJ	ON	2007/12/12 09:39
S29	18	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8)	US-PGPUB; USPAT	ADJ	ON	2008/09/25 13:55
S30	19	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8 or non recrystal\$8)	US-PGPUB; USPAT	ADJ	ON	2008/09/25 13:56
S31	758	(tantalum or ta) same \$5recrystal\$8	US-PGPUB; USPAT	ADJ	ON	2008/09/25 14:05
S32	140	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4	US-PGPUB; USPAT	ADJ	ON	2008/09/25 14:06
S33	71	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and target	US-PGPUB; USPAT	ADJ	ON	2008/09/25 14:07

S34	67	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and sputter \$3	US-PGPUB; USPAT	ADJ	ON	2008/09/25 14:07
S35	22	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 14:49
S36	0	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8)	JPO	ADJ	ON	2008/09/25 14:50
S37	77	(non recrystal\$8 or non-recrystal\$8 or nonrecrystal\$8)	JPO	ADJ	ON	2008/09/25 14:50
S38	0	(non recrystal\$8 or non-recrystal\$8 or nonrecrystal\$8) and (tantalum or ta)	JPO	ADJ	ON	2008/09/25 14:50
S39	0	(non recrystal\$8 or non-recrystal\$8 or nonrecrystal\$8) and (sputter)	JPO	ADJ	ON	2008/09/25 14:50
S40	1	(non recrystal\$8 or non-recrystal\$8 or nonrecrystal\$8) and (sputter\$5)	JPO	ADJ	ON	2008/09/25 14:50
S41	1	(non recrystal\$8 or non-recrystal\$8 or nonrecrystal\$8) and target	JPO	ADJ	ON	2008/09/25 14:51
S42	1	"08269701"	JPO	ADJ	ON	2008/09/25 15:13
S43	24	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8 or non recrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:15
S44	19	"6348139"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:18
S45	55	"6348113"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:20
S46	1449	(tantalum or Ta) with target and (anneal\$4 same temperature)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:29
S47	167	(tantalum or Ta) with target and (anneal\$4 same temperature) and \$5recrystal\$8	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:29

S48	160	(tantalum or Ta) with target and (anneal\$4 same temperature) and \$5recrystal\$8 and sputter \$3	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:29
S49	3	(tantalum or Ta) with target and (anneal\$4 same temperature) and non-recrystal\$8 and sputter\$3	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:32
S50	4	(tantalum or Ta) with target and (anneal\$4) and non-recrystal\$8 and sputter\$3	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:46
S51	5	(tantalum or Ta) with target and (anneal\$4) and non-recrystal\$8	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:47
S52	5	(tantalum or Ta) with target and (anneal\$4) and (nonrecrystal\$8 or non recrystal\$8 or non-recrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:49
S53	32	target and (anneal\$4) and (nonrecrystal\$8 or non recrystal\$8 or non-recrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:49
S54	91	Yamakoshi.in. and target	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:51
S55	1	Yamakoshi.in. and target and (nonrecrystal\$8 or non recrystal\$8 or non-recrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:52
S56	7	target same (nonrecrystal \$8 or non recrystal\$8 or non-recrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:52
S57	6	(tantalum or ta) same (nonrecrystal\$8 or non recrystal\$8 or non-recrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:55
S58	24	(tantalum or ta) and (nonrecrystal\$8 or non recrystal\$8 or non-recrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 15:56
S59	57	(nonrecrystal\$8 or non recrystal\$8 or non-recrystal\$8) same anneal \$5	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 16:01
S60	7	"6566161"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2008/09/25 18:01

S61	17	("3930895" "4111721"). PN. OR ("4334935"). URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/09/26 10:41
S62	4458	(tantalum or ta) same (sputter\$5) same target	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/09/26 11:28
S63	1135	(tantalum or ta) same (sputter\$5) same target and (anneal\$4 same \$5crystal\$8)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/09/26 11:29
S64	42	(tantalum or ta) same (sputter\$5) same target and (anneal\$4 same \$5crystal\$8) and (tantalum or ta).ti.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/09/26 11:30
S65	13	recrystalli\$6 with temperature with (below or less) same (tantalum or Ta) same sputter\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/03 23:09
S66	13	recrystalli\$6 with temperature with (below or less or under) same (tantalum or Ta) same sputter\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/03 23:17
S67	537	(non recrystalli\$6) or (non-recrystalli\$6)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/03 23:24
S68	30	S67 and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/03 23:24
S69	6	S68 and sputter\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/03 23:24
S70	15	("20020063056" "20070062806" "20070062807" "6197134" "6323055" "6759143" "6770154" "6893513").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/04 09:28
S71	68	(tantalum or Ta) with sputter\$3 same \$4recrystalli\$6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/04 09:53
S72	81	(tantalum or Ta) same (\$4recrystalli\$6 with (percent or percentage or "%"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/04 10:15

S73	28	S72 and sputter\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/04 10:17
S75	24	"6348139"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/04 12:28
S76	39	("4525417" "4619695" "4663120" "4762558" "4842706" "4889745" "4960163" "5074907" "5087297" "5282946" "5330701" "5400633" "5418071" "5468401" "5508000" "5513512" "5590389" "5600989" "5608911" "5673581" "5693203" "5772860" "5780755" "5798005" "5809393" "5993575" "5993621").PN. OR ("6348139").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2009/06/04 12:29
S77	2	"20010054457"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2009/06/04 12:50
S78	150	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4	US-PGPUB; USPAT	ADJ	ON	2009/06/04 17:53
S79	800	(tantalum or ta) same \$5recrystal\$8	US-PGPUB; USPAT	ADJ	ON	2009/06/04 17:53
S80	22	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8 or non recrystal\$8)	US-PGPUB; USPAT	ADJ	ON	2009/06/04 17:53
S81	80	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and target	US-PGPUB; USPAT	ADJ	ON	2009/06/04 17:53
S82	77	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and sputter \$3	US-PGPUB; USPAT	ADJ	ON	2009/06/04 17:53
S83	25	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2009/06/04 17:53
S84	501	(tantalum or ta) same target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 16:23

S85	102	(tantalum or ta) same sputtering target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 16:23
S86	3	(tantalum or ta) sputtering target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 16:24
S87	1	"7179704"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 16:34
S88	1	"20030019326"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 16:38
S89	1	S88 and amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 16:38
S90	9	"6566161"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 16:41
S91	1	"9966100"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 16:48
S92	4	"0031310"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 16:53
S93	18	"6193821"	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/25 17:13
S94	4	"200031310"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/02/26 12:35
S95	5	"0031310"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/02/26 12:35
S96	73	148/668.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2010/02/26 12:38
S97	322	204/298.12.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2010/02/26 12:38
S98	162	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4	US-PGPUB; USPAT	ADJ	ON	2010/02/26 12:39
S99	839	(tantalum or ta) same \$5recrystal\$8	US-PGPUB; USPAT	ADJ	ON	2010/02/26 12:39
S100	26	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8 or non recrystal\$8)	US-PGPUB; USPAT	ADJ	ON	2010/02/26 12:39

S101	87	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and target	US-PGPUB; USPAT	ADJ	ON	2010/02/26 12:39
S102	84	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and sputter \$3	US-PGPUB; USPAT	ADJ	ON	2010/02/26 12:39
S103	30	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/02/26 12:39
S104	72	(tantalum or Ta) with sputter\$3 same \$4recrystalli\$6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/02/26 12:40
S105	84	(tantalum or Ta) same (\$4recrystalli\$6 with (percent or percentage or "%"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/02/26 12:40
S106	30	S105 and sputter\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/02/26 12:40
S107	0	amorphous with (tantalum or Ta) sputtering target	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 09:15
S108	3	amorphous same (tantalum or Ta) sputtering target	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 09:15
S109	1	"20070102288"	US-PGPUB; USPAT	ADJ	ON	2010/10/20 10:30
S110	532	(tantalum or ta) same target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/10/20 12:42
S111	356	(tantalum or ta) with target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/10/20 12:42
S112	107	(tantalum or ta) same sputtering target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/10/20 12:43
S113	3	(tantalum or ta) sputtering target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/10/20 12:43
S114	77	148/668.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2010/10/20 12:43
S115	334	204/298.12.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2010/10/20 12:43

S116	167	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4	US-PGPUB; USPAT	ADJ	ON	2010/10/20 12:43
S117	868	(tantalum or ta) same \$5recrystal\$8	US-PGPUB; USPAT	ADJ	ON	2010/10/20 12:44
S118	29	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8 or non recrystal\$8)	US-PGPUB; USPAT	ADJ	ON	2010/10/20 12:44
S119	90	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and target	US-PGPUB; USPAT	ADJ	ON	2010/10/20 12:44
S120	88	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and sputter \$3	US-PGPUB; USPAT	ADJ	ON	2010/10/20 12:44
S121	33	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2010/10/20 12:44
S122	75	(tantalum or Ta) with sputter\$3 same \$4recrystalli\$6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 12:44
S123	86	(tantalum or Ta) same (\$4recrystalli\$6 with (percent or percentage or "%"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 12:44
S124	30	S123 and sputter\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 12:44
S125	54	michaluk.in. and christopher.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 12:54
S126	45	S125 and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 12:55
S127	20	maguire.in. and james.in. and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 12:56
S128	8	kawchak.in. and mark.in. and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 12:57

S129	22	huber.in. and louis.in. and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2010/10/20 12:58
S130	0	amorphous with (tantalum or Ta) sputtering target	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 15:22
S131	3	amorphous same (tantalum or Ta) sputtering target	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 15:22
S132	554	(tantalum or ta) same target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/04/11 16:03
S133	374	(tantalum or ta) with target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/04/11 16:03
S134	110	(tantalum or ta) same sputtering target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/04/11 16:04
S135	3	(tantalum or ta) sputtering target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/04/11 16:04
S136	77	148/668.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2011/04/11 16:04
S137	345	204/298.12.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2011/04/11 16:04
S138	172	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4	US-PGPUB; USPAT	ADJ	ON	2011/04/11 16:04
S139	897	(tantalum or ta) same \$5recrystal\$8	US-PGPUB; USPAT	ADJ	ON	2011/04/11 16:05
S140	33	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8 or non recrystal\$8)	US-PGPUB; USPAT	ADJ	ON	2011/04/11 16:05
S141	91	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and target	US-PGPUB; USPAT	ADJ	ON	2011/04/11 16:05
S142	89	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and sputter \$3	US-PGPUB; USPAT	ADJ	ON	2011/04/11 16:05
S143	89	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and sputter \$3	US-PGPUB; USPAT	ADJ	ON	2011/04/11 16:06

S144	37	(tantalum or ta) and (non-recrystallized\$8 or nonrecrystallized\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/04/11 16:06
S145	77	(tantalum or Ta) with sputter\$3 same \$4recrystallized\$6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 16:06
S146	88	(tantalum or Ta) same (\$4recrystallized\$6 with (percent or percentage or "%"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 16:06
S147	32	S146 and sputter\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 16:06
S148	54	michaluk.in. and christopher.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 16:06
S149	45	S148 and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 16:06
S150	20	maguire.in. and james.in. and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 16:06
S151	8	kawchak.in. and mark.in. and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 16:06
S152	22	huber.in. and louis.in. and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/04/11 16:06
S153	3	amorphous same (tantalum or Ta) sputtering target	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/09/23 13:05
S154	577	(tantalum or ta) same target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/09/23 13:05
S155	390	(tantalum or ta) with target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/09/23 13:05
S156	114	(tantalum or ta) same sputtering target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/09/23 13:05

S157	3	(tantalum or ta) sputtering target same amorphous	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/09/23 13:05
S158	79	148/668.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2011/09/23 13:06
S159	352	204/298.12.ccls. and (tantalum or ta)	US-PGPUB; USPAT	ADJ	ON	2011/09/23 13:06
S160	177	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4	US-PGPUB; USPAT	ADJ	ON	2011/09/23 13:06
S161	925	(tantalum or ta) same \$5recrystal\$8	US-PGPUB; USPAT	ADJ	ON	2011/09/23 13:06
S162	36	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8 or non recrystal\$8)	US-PGPUB; USPAT	ADJ	ON	2011/09/23 13:06
S163	92	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and target	US-PGPUB; USPAT	ADJ	ON	2011/09/23 13:06
S164	91	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and sputter \$3	US-PGPUB; USPAT	ADJ	ON	2011/09/23 13:06
S165	91	(tantalum or ta) same \$5recrystal\$8 and anneal \$3 and roll\$4 and sputter \$3	US-PGPUB; USPAT	ADJ	ON	2011/09/23 13:06
S166	40	(tantalum or ta) and (non-recrystal\$8 or nonrecrystal\$8)	US-PGPUB; USPAT; USOCR; EPO; JPO	ADJ	ON	2011/09/23 13:07
S167	79	(tantalum or Ta) with sputter\$3 same \$4recrystalli\$6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/09/23 13:07
S168	89	(tantalum or Ta) same (\$4recrystalli\$6 with (percent or percentage or "%"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/09/23 13:07
S169	33	S168 and sputter\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/09/23 13:07
S170	54	michaluk.in. and christopher.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/09/23 13:07
S171	45	S170 and (tantalum or Ta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2011/09/23 13:07

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